

AMENDMENTS TO THE CLAIMS

This listing of claims will replace all prior versions and listings of claims in the application:

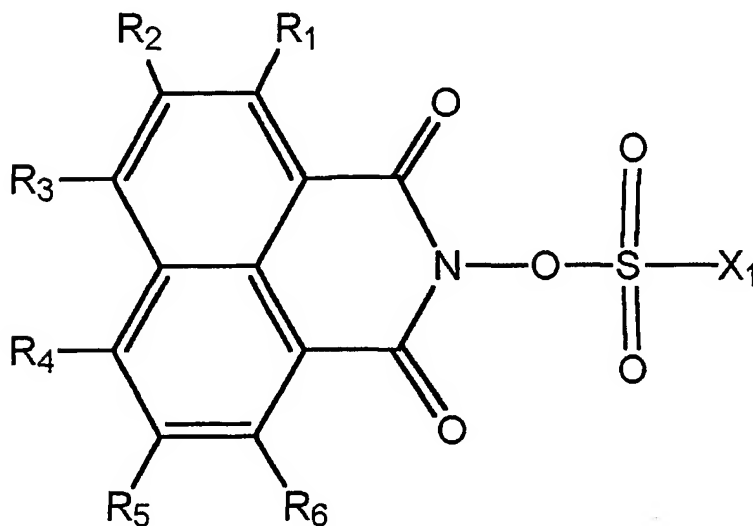
LISTING OF CLAIMS:

1. (Currently amended) A positive working photosensitive admixture composition comprising:

an epoxy compound having two or more epoxy groups in one molecule;

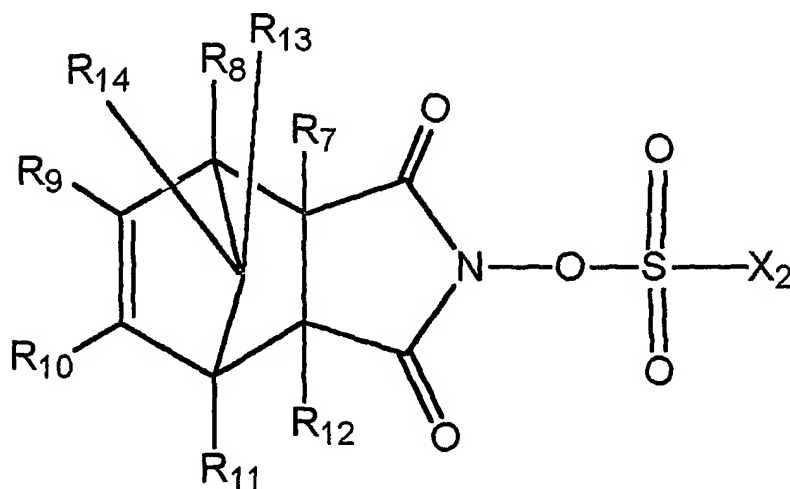
a curing catalyst or a compound for producing a curing catalyst by heat; and
sulfonates.

2. (Original) A composition according to Claim 1, wherein the sulfonates are at least one compound selected from the group consisting of a compound represented in the following formulae (1) to (7),



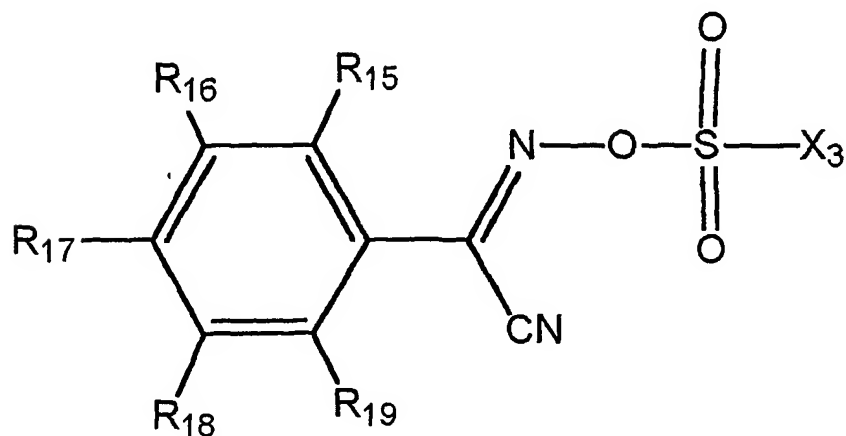
(1)

wherein X_1 is an optionally substituted monovalent organic group with a carbon number of 1 to 20, and R_1 to R_6 are each independently a hydrogen atom or a monovalent organic group,



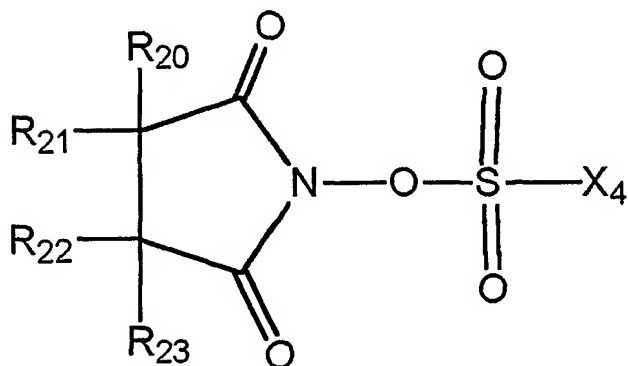
(2)

wherein X_2 is an optionally substituted monovalent organic group with a carbon number of 1 to 20, and R_7 to R_{14} are each independently a hydrogen atom or a monovalent organic group,



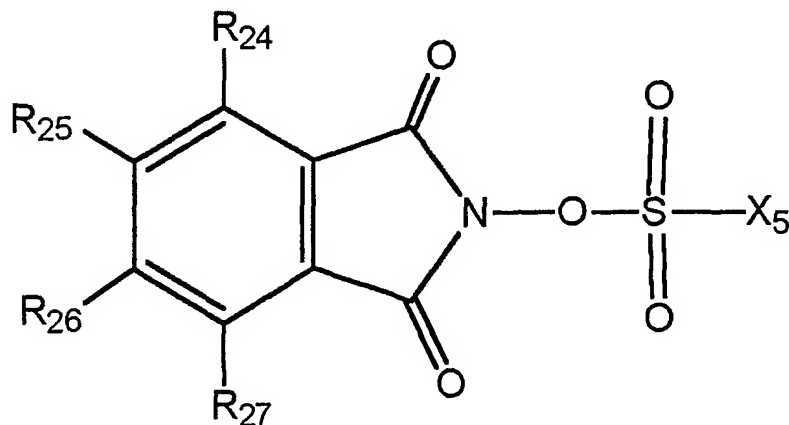
(3)

wherein X_3 is an optionally substituted monovalent organic group with a carbon number of 1 to 20, and R_{15} to R_{19} are each independently a hydrogen atom, an alkoxy group or a monovalent organic group,



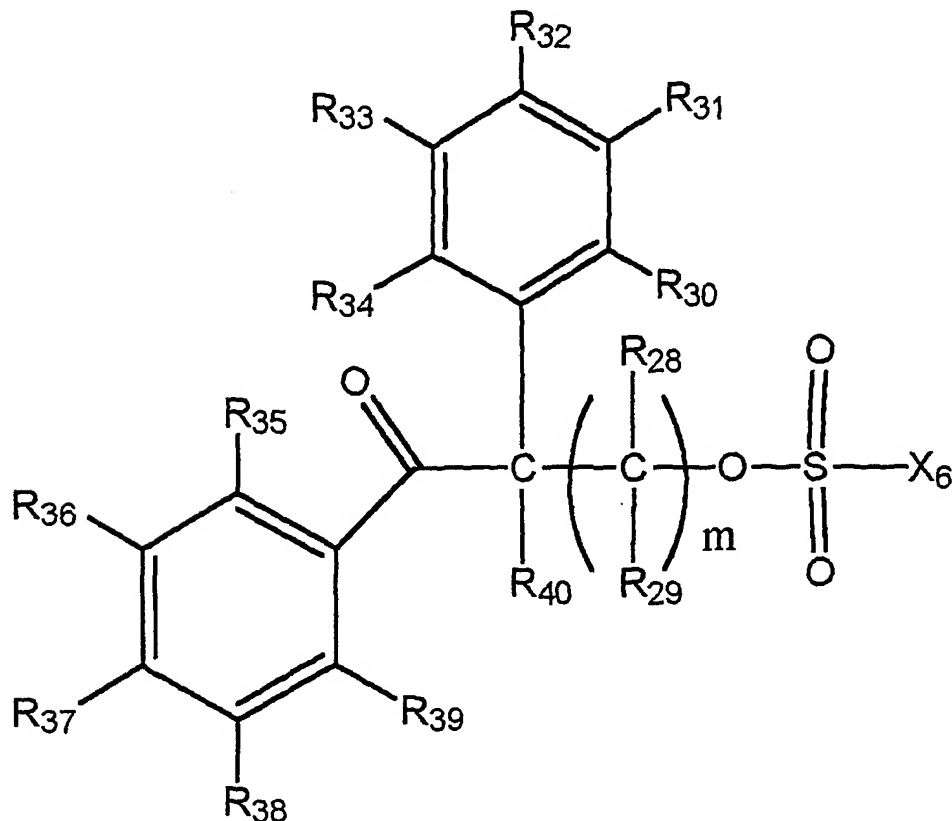
(4)

wherein X_4 is an optionally substituted monovalent organic group with a carbon number of 1 to 20, and R_{20} to R_{23} are each independently a hydrogen atom or a monovalent organic group,



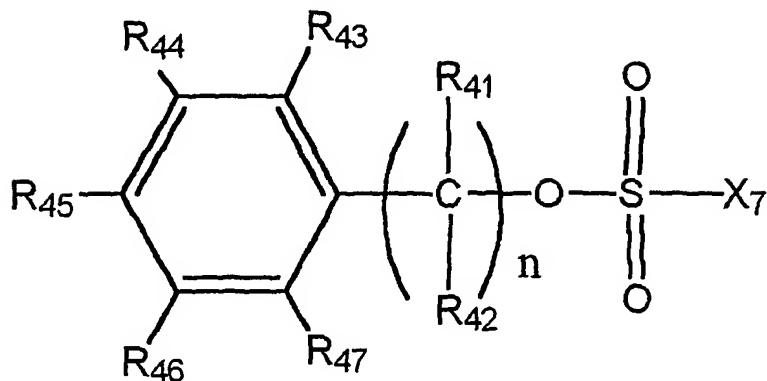
(5)

wherein X_5 is an optionally substituted monovalent organic group with a carbon number of 1 to 20, and R_{24} to R_{27} are each independently a hydrogen atom or a monovalent organic group,



(6)

wherein X_6 is an optionally substituted monovalent organic group with a carbon number of 1 to 20, R_{28} to R_{39} are each independently a hydrogen atom or a monovalent organic group, R_{40} is a hydrogen atom or a hydroxyl group, and m is 0 or 1,



(7)

wherein X₇ is an optionally substituted monovalent organic group, R₄₁ and R₄₂ are each independently a hydrogen atom or a monovalent organic group with a carbon number of 1 to 20, R₄₃ to R₄₇ are each independently a hydrogen atom, a nitro group or a monovalent organic group with a carbon number of 1 to 20, and n is 0 or 1.

3. (Original) A method of manufacturing a member for a semiconductor comprising the steps of:

applying a positive working photosensitive composition according to Claim 1 on a substrate to expose;

curing an unexposed part thereof by heat; and

developing an exposed part thereof.

4. (Original) A method of manufacturing a member for a display comprising the steps of:

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Attorney Docket No. Q78068

applying a positive working photosensitive composition according to Claim 1 on a
substrate to expose;

curing an unexposed part thereof by heat; and

developing an exposed part thereof.